ABSTRACT OF DISCLOSURE

An etchant fume exhaust apparatus is installed in a system performing an etching process during fabrication of LCDs. The etchant fume exhaust apparatus prevents the contamination and corrosion of the etching system by allowing both gaseous and liquid etchant to be discharged safely. The etchant fume exhaust apparatus includes an exhaust hole that provides a passage to discharge gaseous etchant, an exhaust plate located under the exhaust hole that collects condensed etchant dripping from the exhaust hole, a support part that fixes the exhaust plate to the exhaust hole, and an exhaust line connected to the bottom of the exhaust plate through which the etchant collected in the exhaust plate is removed from the etchant plate.